

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No. 09/546,174	Confirmation No.: 4793
Application of: Chih-Chien Liu, Ta-Shan Tseng, W. B. Shieh, J. Y. Wu, Water Lur and Shih-Wei Sun	Art Unit: 1711
Filed: April 11, 2000	Examiner: Sergent, Rabon A.
Attorney Docket No. UMC-96-279 CON	Customer No.: 25235
For: HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION PROCESS	

RESPONSE TO OFFICE ACTION DATED SEPTEMBER 8, 2006

MAIL STOP RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This response is filed with a request for continued examination and a petition for two month extension of the period for response the office communication mailed September 8, 2006. Please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims beginning on page 2 of this paper.

Remarks begin on page 11 of this paper.